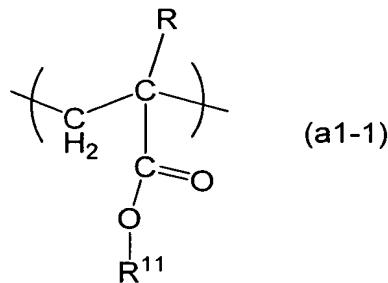


CLAIMS

1. A resin for a resist, comprising structural units (a) derived from an (α -lower alkyl)acrylate ester as a principal component, wherein

5 said structural units (a) comprise structural units (a1) derived from an (α -lower alkyl)acrylate ester comprising an acid dissociable, dissolution inhibiting group, and structural units (a2-1) derived from an (α -lower alkyl)acrylate ester comprising a lactone-containing monocyclic group, and

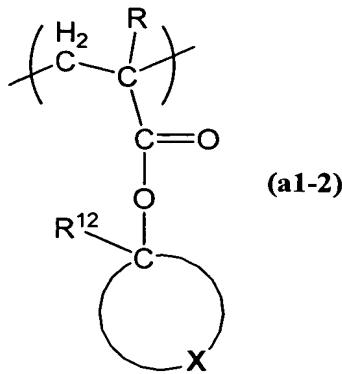
10 said structural units (a1) comprise structural units (a1-1) derived from an (α -lower alkyl)acrylate ester and represented by a general formula (a1-1) shown below:



[wherein, R represents a hydrogen atom or a lower alkyl group, and R¹¹ represents an acid dissociable, dissolution inhibiting group that comprises a monocyclic aliphatic hydrocarbon group and comprises no polycyclic aliphatic hydrocarbon groups].

15

2. A resin for a resist according to claim 1, wherein said structural units (a1-1) comprise structural units (a1-2) represented by a general formula (a1-2) shown below:



[wherein, R represents a hydrogen atom or a lower alkyl group, R¹² represents a lower alkyl group, and X represents a group which, in combination with a carbon atom to which said group R¹² is bonded, forms a monocyclic aliphatic hydrocarbon group].

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3. A resin for a resist according to claim 1, wherein said structural units (a) also comprise structural units (a3) derived from an (α -lower alkyl)acrylate ester that comprises a polar group-containing aliphatic hydrocarbon group.

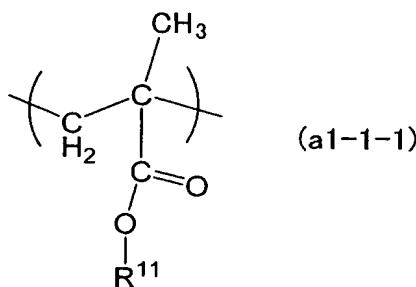
10 4. A resin for a resist according to claim 1, wherein said structural units (a) also comprise other structural units (a4) derived from an (α -lower alkyl)acrylate ester that comprises a polycyclic aliphatic hydrocarbon group, which differ from said structural units (a2) and (a3).

15 5. A positive resist composition comprising: (A) a resist resin component that exhibits increased alkali solubility under action of acid, and (B) an acid generator component that generates acid on exposure, wherein
said component (A) comprises a resin for a resist according to claim 1.

6. A positive resist composition according to claim 5, further comprising a nitrogen-containing organic compound.

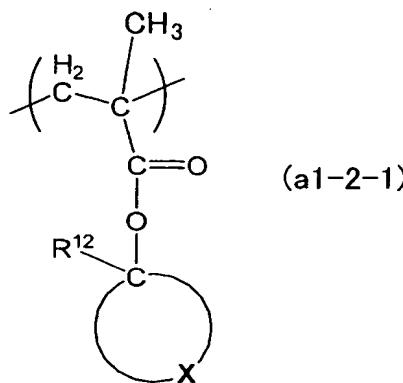
7. A method of forming a resist pattern, comprising the steps of: forming a positive
5 resist film on top of a substrate using a positive resist composition according to claim 5,
conducting a selective exposure treatment of said positive resist film, and performing
alkali developing to form a resist pattern.

8. A resin for a resist, comprising structural units (a) derived from an (α -lower
10 alkyl)acrylate ester as a principal component, wherein
said structural units (a) comprise structural units (a1) derived from an (α -lower
alkyl)acrylate ester comprising an acid dissociable, dissolution inhibiting group, and
structural units (a2) derived from an (α -lower alkyl)acrylate ester comprising a lactone-
containing monocyclic or polycyclic group, and
15 said structural units (a1) comprise structural units (a1-1-1) derived from a
methacrylate ester and represented by a general formula (a1-1-1) shown below:



[wherein, R¹¹ represents an acid dissociable, dissolution inhibiting group that comprises a
monocyclic aliphatic hydrocarbon group and comprises no polycyclic aliphatic
20 hydrocarbon groups].

9. A resin for a resist according to claim 8, wherein said structural units (a1-1-1) comprise structural units (a1-2-1) represented by a general formula (a1-2-1) shown below:



5 [wherein, R¹² represents a lower alkyl group, and X represents a group which, in combination with a carbon atom to which said group R¹² is bonded, forms a monocyclic aliphatic hydrocarbon group].

10. A resin for a resist according to claim 8, wherein said structural units (a) also 10 comprise structural units (a3) derived from an (α -lower alkyl)acrylate ester that comprises a polar group-containing aliphatic hydrocarbon group.

11. A resin for a resist according to claim 8, wherein said structural units (a) also comprise other structural units (a4) derived from an (α -lower alkyl)acrylate ester that 15 comprises a polycyclic aliphatic hydrocarbon group, which differ from said structural units (a2) and (a3).

12. A positive resist composition comprising: (A) a resist resin component that exhibits increased alkali solubility under action of acid, and (B) an acid generator component that generates acid on exposure, wherein
said component (A) comprises a resin for a resist according to claim 8.

5

13. A positive resist composition according to claim 12, further comprising a nitrogen-containing organic compound.

14. A method of forming a resist pattern, comprising the steps of: forming a positive
10 resist film on top of a substrate using a positive resist composition according to claim 12,
conducting a selective exposure treatment of said positive resist film, and performing
alkali developing to form a resist pattern.